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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Takahiro KISHIOKA

Group Art Unit: 1756

Application No.: 10/551,130

Filed: September 29, 2005

Docket No.: 125473

For: COMPOSITION FOR FORMING UNDERLAYER COATING FOR LITHOGRAPHY  
CONTAINING EPOXY COMPOUND AND CARBOXYLIC ACID COMPOUND

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. Relevance of one or more non-English language reference is discussed in the present specification. See References 9-15.
- 3. One or more reference cited herein was cited in the International Search Report. An English language version of the International Search Report is attached for the Examiner's information. See References 16-25.
- 4. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- 5. An English language Abstract of one or more non-English language reference is attached hereto. See References 9-25.
- 6. A computer-generated English language translation of one or more Japanese Patent Publication cited herein has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See References 9-11, 13, 14 & 16-25.

7. Reference 3 corresponds to reference 16. Reference 4 corresponds to reference 17. Reference 5 corresponds to reference 18. Reference 6 corresponds to reference 20. Reference 7 corresponds to reference 22. Reference 8 corresponds to reference 23.

Respectfully submitted,



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PATENT & TRADEMARK OFFICE USPTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130	
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)		APPLICANT Takahiro KISHIOKA				
				FILING DATE September 29, 2005	GROUP 1756	
U.S. PATENT DOCUMENTS						
Examiner Initials	Cite No.	Document Number	Date	Name		
	1	US 5,919,599	7/6/1999	Meador et al.		
	2	US 5,693,691	12/2/1997	Flair et al.		
	3	US 6,114,085	9/5/2000	Padmanaban et al.		
	4	US 6,388,039 B1	5/14/2002	Jung et al.		
	5	US 6,492,092 B1	12/10/2002	Foster et al.		
	6	US 2002/0093069 A1	7/18/2002	Hong et al.		
	7	US 2002/0127789 A1	9/12/2002	Hong et al.		
	8	US 2002/0009595 A1	1/24/2002	Hong et al.		
FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract <input checked="" type="checkbox"/> X	With English Translation <input checked="" type="checkbox"/> X
	9	JP A 2000-294504	10/20/2000	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	10	JP A 2002-47430	2/12/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	11	JP A 2002-190519	7/5/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	12	WO 02/05035 A1	1/17/2002	WIPO	<input checked="" type="checkbox"/> X	
	13	JP A 2002-128847	5/9/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	14	JA A 11-279523	10/12/1999	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	15	WO 02/086624 A1	10/31/2002	WIPO	<input checked="" type="checkbox"/> X	
	16	JP A 2002-530696	9/17/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	17	JP A 2001-49231	2/20/2001	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	18	JP A 2002-539282	11/19/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	19	JP A 10-333336	12/18/1998	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	20	JP A 2002-105137	4/10/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	21	JP A 6-35201	2/10/1994	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	22	JP A 2002-97231	4/2/2002	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	23	JP A 2001-194799	7/19/2001	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	24	JP A 10-120939	5/12/1998	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X
	25	JP A 6-118656	4/28/1994	Japan	<input checked="" type="checkbox"/> X	<input checked="" type="checkbox"/> X



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Form PTO-1449 (REV. 1/06) <b>PATENT &amp; TRADEMARK OFFICE</b>		US Dept. of Commerce <b>PATENT &amp; TRADEMARK OFFICE</b>	ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130
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		FILING DATE September 29, 2005	GROUP 1756	
OTHER DOCUMENTS				
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)		
	26	Lynch et al.; "Properties and Performance of Near UV Reflectivity Control Layers;" Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229.		
	27	Taylor et al.; "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography;" Proceedings of SPIE, March 1999, Vol. 3678, pp. 174-185.		
	28	Meador et al.; "Recent Progress in 193 nm Antireflective Coatings;" Proceedings of SPIE, March 1999, Vol 3678, pp. 800-809.		
EXAMINER			DATE CONSIDERED	
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.				